



Serial No. 09/988,302

SEC.910

Amendment dated 10 September 2004

**THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re PATENT APPLICATION of:

Kyoung-Hwan CHIN et al.

Group Art Unit: 1746

Serial No.: 09/988,302

Examiner: Gentle WINTER

Filed: 19 November 2001

CLEANING APPARATUS OF A  
HIGH DENSITY PLASMA  
CHEMICAL VAPOR DEPOSITION  
CHAMBER AND CLEANING  
METHOD THEREOF

*Do not enter*

*10/15/04*  
*Ok to enter*  
*JB*

**COMBINED REQUEST FOR WITHDRAWAL OF  
FINALITY OF OFFICE ACTION AND  
AMENDMENT UNDER 35 C.F.R. § 1.116**

U.S. Patent and Trademark Office  
220 20th Street S.  
Customer Window, Mail Stop AF  
Crystal Plaza Two, Lobby, Room 1B03  
Arlington, VA 22202

Sir:

In response to the Office Action dated 13 July 2004, the period for response to which extends through 13 October 2004, Applicants respectfully traverse the "finality" of the Office Action. Applicants also respectfully request that the above-identified patent application be amended as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 5 of this paper.